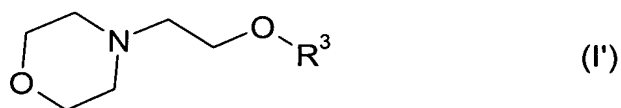
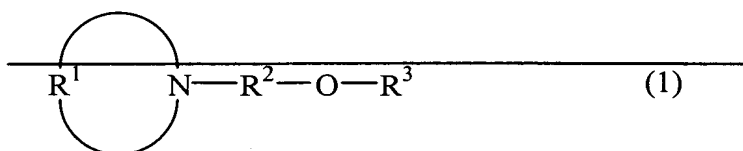


The listing of claims will replace all prior versions, and listings, of claims in the application:

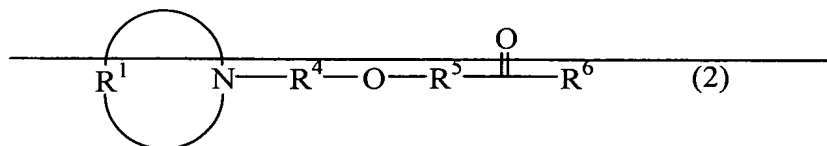
Listing of Claims:

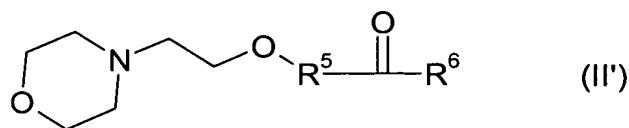
1. (Currently Amended) An amine compound of the following general formula (1) (I'):



wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain at least one carbonyl, ether, ester or sulfide group, R^2 is a straight or branched alkylene group of 1 to 10 carbon atoms, R^3 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which may contain optionally contains a one or more hydroxy groups group, ether groups group, carbonyl groups group, ester groups group, lactone rings ring or carbonate groups group, and R^2 and R^3 , taken together, may form a ring with the oxygen atom.

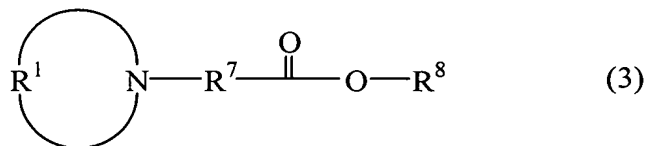
2. (Currently Amended) An amine compound of the following general formula (2) (II'):





wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain at least one carbonyl, ether, ester or sulfide group, R^4 is a straight or branched alkylene group of 1 to 10 carbon atoms, R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which ~~may contain~~ optionally contains a one or more hydroxy groups group, ether groups group, carbonyl groups group, ester groups group, lactone rings ring or carbonate groups group.

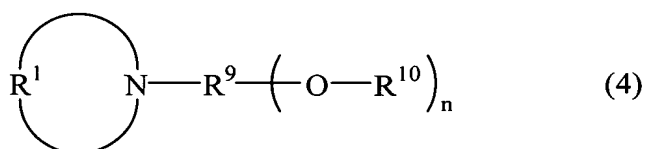
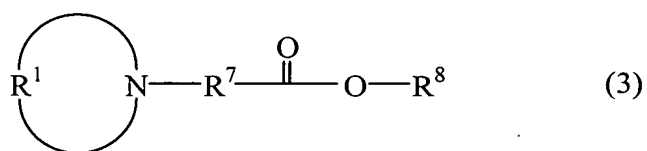
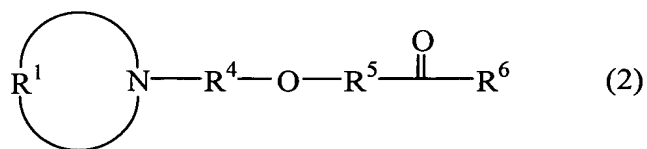
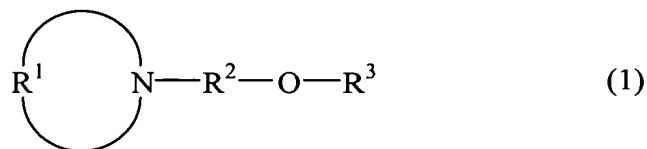
3. (Currently Amended) An amine compound of the following ~~general~~ formula (3):



wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which ~~may contain~~ optionally contains at least one carbonyl, ether, ester or sulfide group, R^7 is a straight or branched alkylene group of 1 to 10 carbon atoms, R^8 is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which ~~may contain~~ optionally contains a one or more hydroxy groups group, ether groups group, carbonyl groups group, ester groups group, lactone rings ring or carbonate groups group, and R^7 and R^8 , taken together, ~~may optionally~~ form a ring with the COO.

4. (Canceled)

5. (Currently Amended) A resist composition comprising at least one of amine compounds compound of the following general formulae (1) to (4):



wherein R¹ is a straight or branched alkylene group of 2 to 20 carbon atoms which ~~may contain~~ optionally contains at least one carbonyl, ether, ester or sulfide group,

R², R⁴ and R⁷ each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R³ and R⁶ ~~each are,~~ each independently, hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which ~~may contain~~ optionally contains a one or more hydroxy ~~groups group~~, ether ~~groups group~~, carbonyl ~~groups group~~, ester ~~groups group~~, lactone ~~rings ring~~ or carbonate ~~groups group~~,

R⁵ is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R⁸ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which ~~may contain~~ optionally contains a one or more hydroxy ~~groups group~~, ether ~~groups group~~, carbonyl ~~groups group~~, ester ~~groups group~~, lactone ~~rings ring~~ or carbonate ~~groups group~~,

R² and R³, taken together, may optionally form a ring with the oxygen atom,

R^7 and R^8 , taken together, may optionally form a ring with the COO,

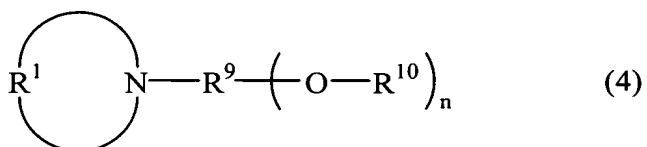
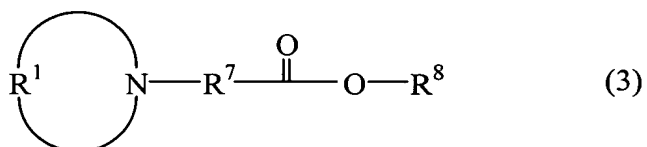
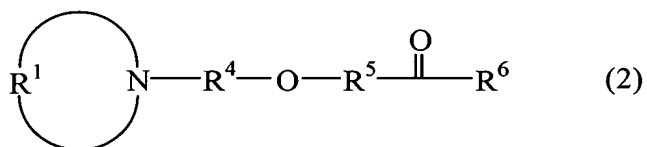
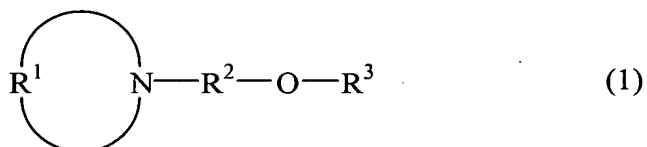
R^9 is a (n+1)-valent organic group of 2 to 10 carbon atoms,

R^{10} which is ~~may be~~ the same or different is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which ~~may contain~~ optionally contains a one or more hydroxy groups ~~group~~, ether groups ~~group~~, carbonyl groups ~~group~~, ester groups ~~group~~, lactone rings ~~ring~~ or carbonate groups ~~group~~, and

n is equal to 2, 3 or 4.

6. (Currently Amended) A positive resist composition comprising

(A) ~~the amine compound of claim 5~~ at least one amine compound of the following formulae (1) to (4):



wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which optionally contains at least one carbonyl, ether, ester or sulfide group,

R^2 , R^4 and R^7 each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R^3 and R^6 are, each independently, hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups,

ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R⁵ is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R⁸ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R² and R³, taken together, optionally form a ring with the oxygen atom,

R⁷ and R⁸, taken together, optionally form a ring with the COO,

R⁹ is a (n+1)-valent organic group of 2 to 10 carbon atoms,

R¹⁰ which is the same or different is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups, and

n is equal to 2, 3 or 4,

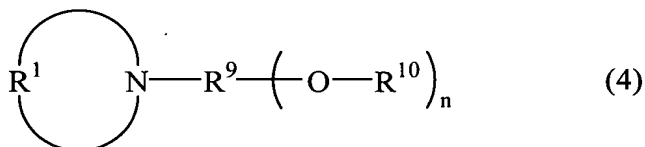
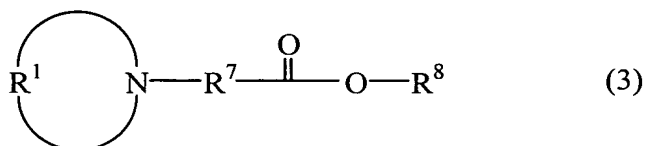
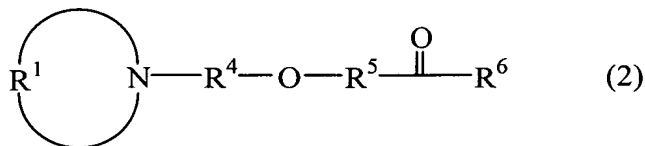
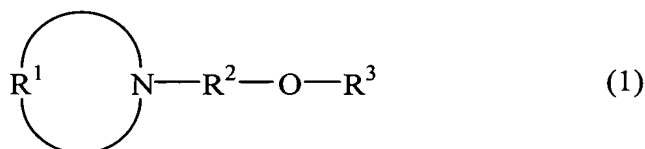
(B) an organic solvent,

(C) a base resin having an acidic functional group protected with an acid labile group, which is normally alkali insoluble or substantially alkali insoluble, but becomes alkali soluble upon elimination of the acid labile group, and

(D) a photoacid generator.

7. (Original) The positive resist composition of claim 6 further comprising (E) a dissolution inhibitor.

8. (Currently Amended) A negative resist composition comprising
 (A) ~~the amine compound of claim 5~~ at least one amine compound of the following
 formulae (1) to (4):



wherein R¹ is a straight or branched alkylene group of 2 to 20 carbon atoms which optionally contains at least one carbonyl, ether, ester or sulfide group,

R², R⁴ and R⁷ each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R³ and R⁶ are, each independently, hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

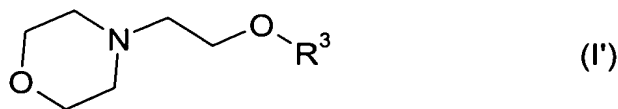
R⁵ is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R⁸ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups,

R² and R³, taken together, optionally form a ring with the oxygen atom,

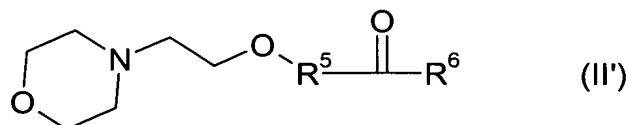
R⁷ and R⁸, taken together, optionally form a ring with the COO,
R⁹ is a (n+1)-valent organic group of 2 to 10 carbon atoms,
R¹⁰ which is the same or different is hydrogen or a straight, branched or cyclic alkyl or
alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups,
ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups, and
n is equal to 2, 3 or 4,
 (B) an organic solvent,
 (C') a base resin which is normally alkali-soluble, but becomes substantially alkali insoluble when crosslinked with a crosslinker,
 (D) a photoacid generator, and
 (F) the crosslinker capable of crosslinking under the action of acid.

9. (Previously Presented) A process for forming a resist pattern comprising the steps of:
 applying the resist composition of claim 5 onto a substrate to form a coating,
 heat treating the coating and then exposing it to high-energy radiation having a wavelength of less than 300 nm or electron beams through a photo mask, and
 optionally heat treating the exposed coating and developing it with a developer.
10. (New) A process for forming a resist pattern comprising the steps of:
 applying the resist composition of claim 6 onto a substrate to form a coating,
 heat treating the coating and then exposing it to high-energy radiation having a wavelength of less than 300 nm or electron beams through a photo mask, and
 optionally heat treating the exposed coating and developing it with a developer.
11. (New) A resist composition according to claim 5, comprising an amine compound of the following formula (I')



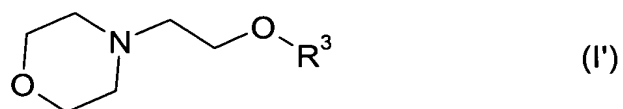
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

12. (New) A resist composition according to claim 5, comprising an amine compound of the following formula (II'):



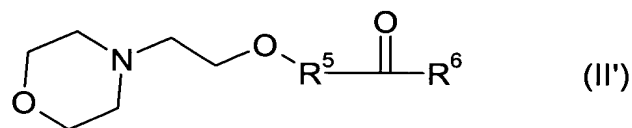
wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

13. (New) A positive resist composition according to claim 6, comprising an amine compound of the following formula (I'):



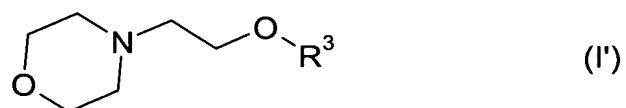
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

14. (New) A positive resist composition according to claim 6, comprising an amine compound of the following formula (II'):



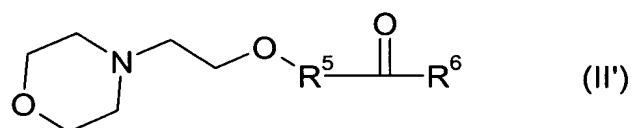
wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

15. (New) A negative resist composition according to claim 8, comprising an amine compound of the following formula (I'):



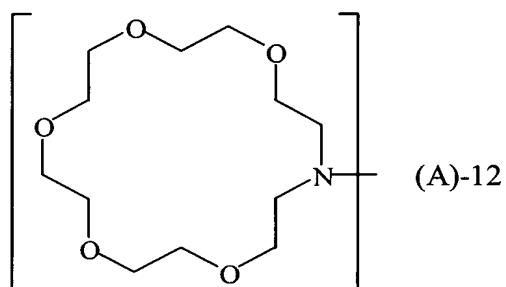
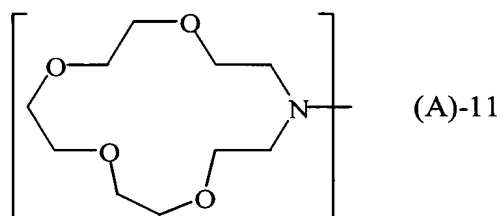
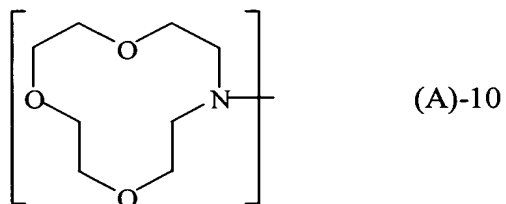
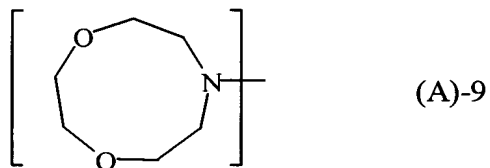
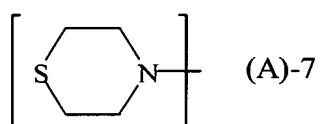
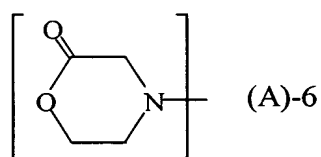
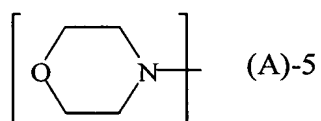
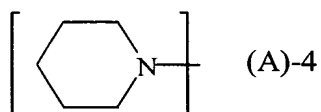
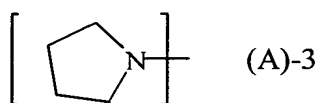
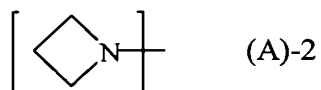
wherein R^3 is hydrogen or a straight, branched or cyclic alkyl which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

16. (New) A negative resist composition according to claim 8, comprising an amine compound of the following formula (II'):



wherein R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which optionally contains one or more hydroxy groups, ether groups, carbonyl groups, ester groups, lactone rings or carbonate groups.

17. (New) A resist composition according to claim 5, comprising an amine compound of formula (3).
18. (New) A positive resist composition according to claim 6, comprising an amine compound of formula (3).
19. (New) A negative resist composition according to claim 8, comprising an amine compound of formula (3).
20. (New) An amine compound according to claim 3, wherein the moiety (A) is a moiety of one of formulae (A)-1 to (A)-12,



or

21. (New) A resist composition comprising an amine compound of claim 20.